

Substitute Form PTO-1449
(Modified)U.S. Department of Commerce
Patent and Trademark OfficeAttorney's Docket No.
17979-034US1Application No.
10/562,257**Information Disclosure Statement
by Applicant**

(Use several sheets if necessary)

(37 CFR 1.98(b))

Applicant
Shafer et al.Filing Date
December 4, 2006Group Art Unit
2621**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	2005/0248856	11/2005	Omura et al.			
	AB	2002/0163629	11/7/2002	Switkes et al.			
	AC	2004/0109237	6/10/2004	Epple et al.			
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	AT	2005/0161644	7/28/2005	Zhang et al.			
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Date Considered

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	ADD	2006/0187430	8/24/2006	Docdoc et al.			
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	AMM	2006/0066962	03/30/06	Totzeck et al.			
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							Yes	No
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	AQQ	WO 2004/057589	7/8/2004	WIPO				
	ARR	WO 2004/107048	12/9/2004	WIPO			English abstract	
	ASS	JP 2000-58436	02/25/2000	Japan			X	
	ATT	WO 2001/50171	07/12/2001	WIPO			English abstract	
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	AVV	WO 2005/059617	6/30/2005	WIPO				
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	AYY	WO 2005/081067	9/1/2005	WIPO				

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Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
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	APPP	EP 1 489 462	12/22/2004	EPO				
	AQQQ	EP 1 630 616	03/01/2006	EPO				

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	ARRR	Burnett et al., "High Index Materials for 193 nm immersion Lithography", International Symposium on Immersion & 157 nm Lithography, February 8, 2004, pp 3, figure 1.
	ASSS	Dammel et al., "193 nm Immersion Lithography – Taking the Plunge", Journal of Photopolymer Science and Technology, vol. 17 no. 4, pp 587-607 (2004).
	ATTT	Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
	AUUU	Owa et al., "Immersion Lithography; its Potential Performance Issues", Proceeding of the SPIE, SPIE, Bellingham, VA, vol. 5040 no. 1, February 28, 2003, pp 724-733.

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Other Documents (include Author, Title, Date, and Place of Publication)		
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	AVVV	Lammers, "'Doped water' could extend 193-nm immersion litho," <i>EETimes Online</i> , http://www.eetimes.com/showArticle.jhtml?articleID=18310517 , 2 pages (January 28, 2004).
	AWWW	Saurei et al., "Design of an autofocus lens for VGA 1/4-inch CCD and CMOS sensors," <i>SPIE International Symposium: Optical Systems Design</i> , St. Etienne, France, 1 page (2003)
	AXXX	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", <i>Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena</i> , American Vacuum Society, New York, NY, Vol. 17, No. 6, November 1999 (199-11) pp 3306-3309.
	AYYY	Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf , (January 28, 2004).

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